

Radiation hardness of n-Si irradiated by fast-pile neutrons

P.G. Litovchenko¹, A.P. Dolgolenko¹, A.P. Litovchenko¹,
M.D. Varentsov¹, V.F. Lastovetsky¹, G.P. Gaidar¹, A. Candelori², D.
Bisello², M. Boscardin³, G. F. Dalla Betta⁴.

¹*Institute for Nuclear Research NASU, av. Nauky 47, UA-03028, Kiev, Ukraine,
Fax: 380/44/2654463, e-mail: plitov@kinr.kiev.ua*

²*Istituto Nazionale di Fisica Nucleare and Dipartimento di Fisica,
Università di Padova, via Marzolo 8, I-35131, Padova, Italy.*

³*ITC-IRST, Divisione Microsistemi, Via Sommarive 18, 38050 Povo (TN), Italy*

⁴*Università di Trento, Dipartimento di Informatica e Telecomunicazioni, via Sommarive 14, 38050,
Povo (TN), Italy*

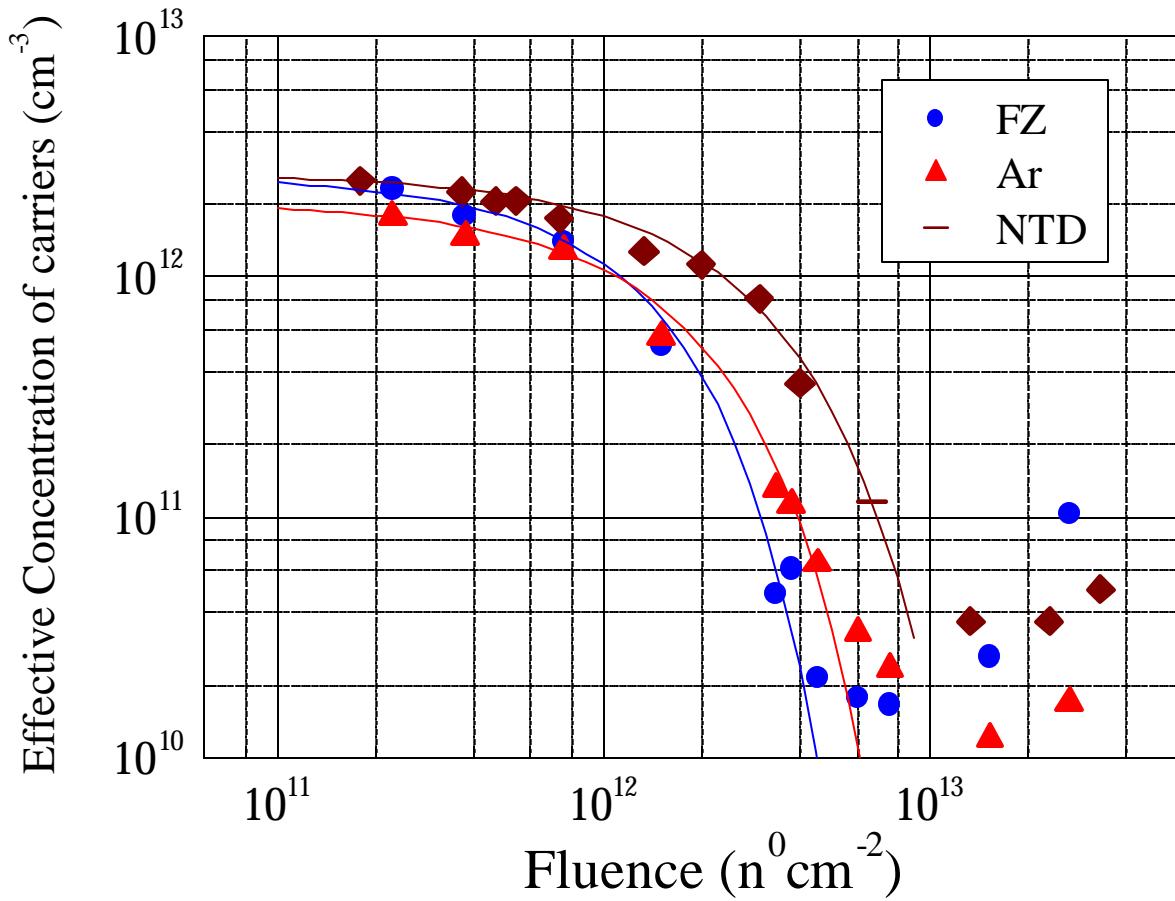


Fig. 1. The dependence of effective concentration of electrons at room temperature on the fluence of fast-pile neutrons in • - n-Si(FZ), ? - n-Si(Ar), ♦ - n-Si(NTD)

The average concentration of carriers (\bar{n}_0) in n-Si for: (FZ)- $2.65 \cdot 10^{12}$; (Ar)- $2.04 \cdot 10^{12}$; (NTD)- $2.69 \cdot 10^{12} \text{ cm}^{-3}$; (ISV) - 1.9×10^{12} ; (SV) - 9.5×10^{11} ; (Top) - $2.7 \times 10^{11} \text{ cm}^{-3}$.

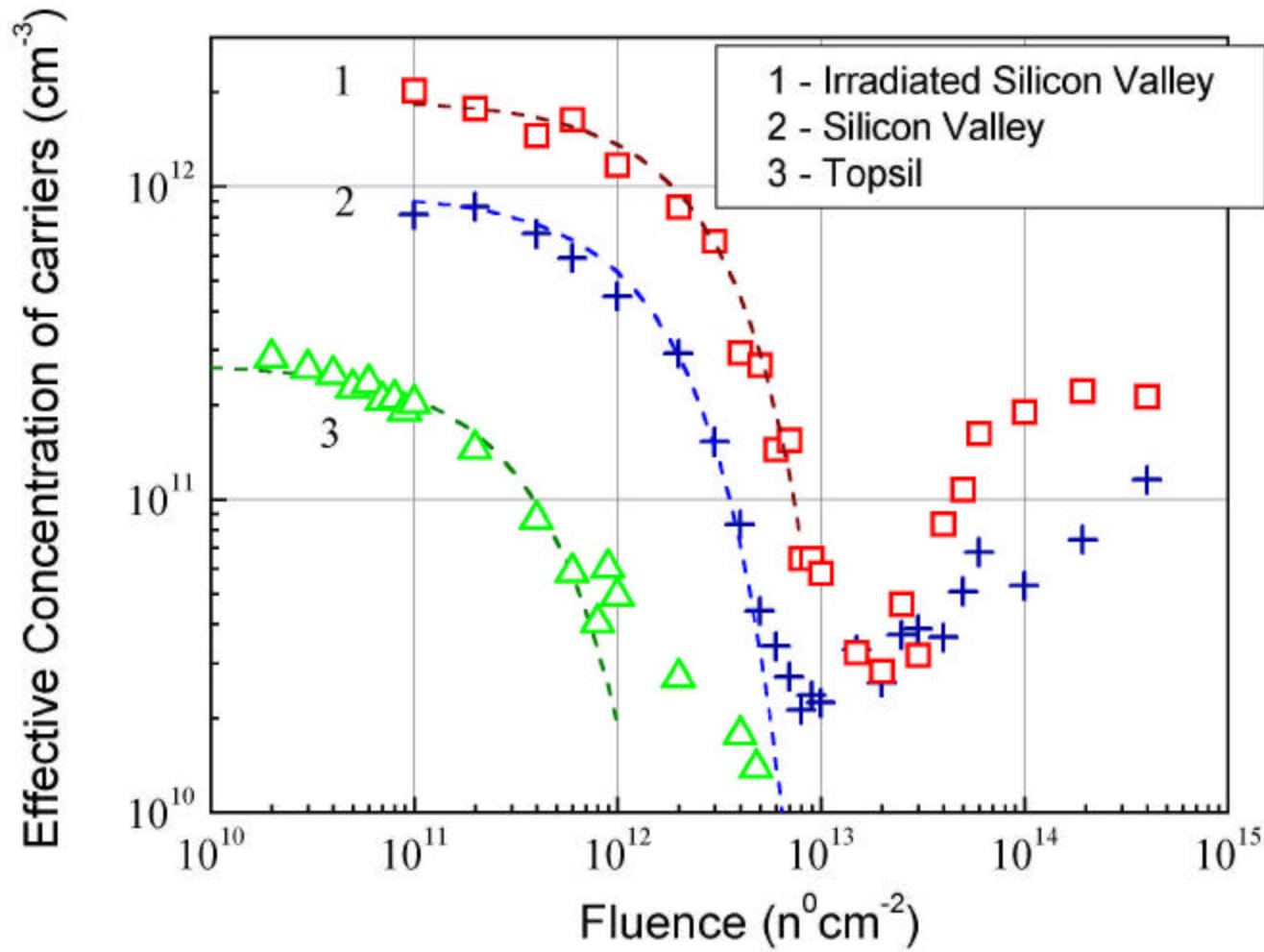


Fig. 2. The dependence of effective concentration of electrons at room temperature on the fluence of fast-pile neutrons for 1 - n-Si(ISV), 2 - n-Si(SV) 3 - n-Si(Top)

The average concentration of carriers (\bar{n}_o) in n-Si for: (FZ)- $2.65 \cdot 10^{12}$; (Ar)- $2.04 \cdot 10^{12}$; (NTD)- $2.69 \cdot 10^{12}$ cm⁻³; (ISV) - 1.9×10^{12} ; (SV) - 9.5×10^{11} ; (Top) - 2.7×10^{11} cm⁻³.

Table 1. The introduction rates of radiation defects v_i (E_c - 0.43 eV) and n_j (E_c - 0.315 eV) and parameters of defect clusters: R_1 and m used for description (in grown by various methods (FZ, Ar, NTD) n-Si with average concentration of carriers (\bar{n}_o) before the irradiation) the dependence of effective concentration of carriers on the fluence of fast-pile neutrons (2)

<i>Si sample</i>	<i>T, K</i>	$\bar{n}_o, \text{cm}^{-3}$	v_i, cm^{-1} ($E_c - 0.43 \text{ eV}$)	n_j, cm^{-1} ($E_c - 0.315 \text{ eV}$)	<i>meV</i>	$R_1 \text{\AA}$
FZ	294.4	$2.65 \cdot 10^{12}$	1.16	0.66	0.528	92
Ar	294.4	$2.04 \cdot 10^{12}$	0.46	0.66	0.523	76
NTD	298.5	$2.69 \cdot 10^{12}$	0.26	0.79	0.511	76

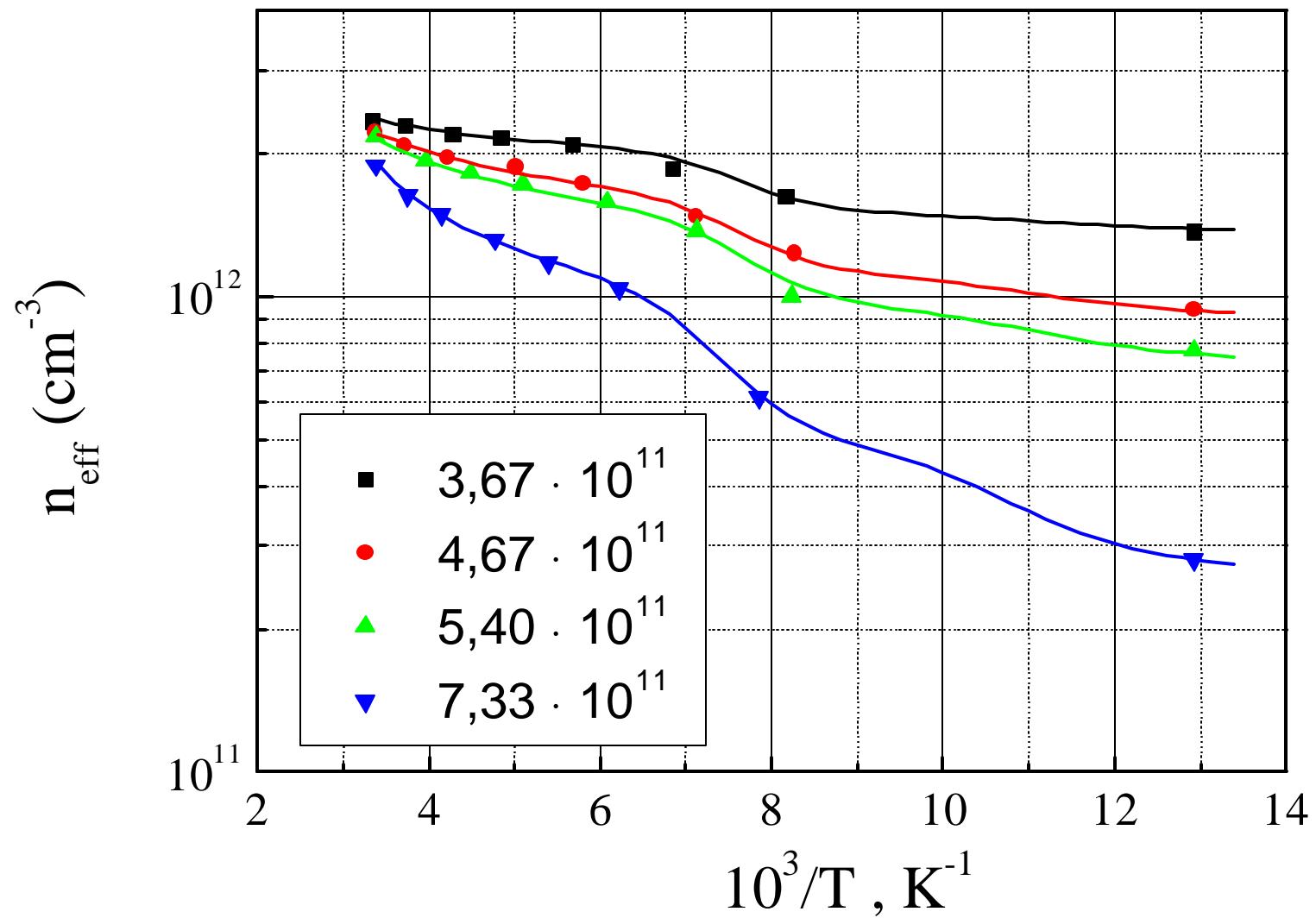


Fig. 3. The dependence of effective concentration of electrons on reciprocal temperature for n-Si (NTD) after irradiation by the fluence of fast-pile neutrons:

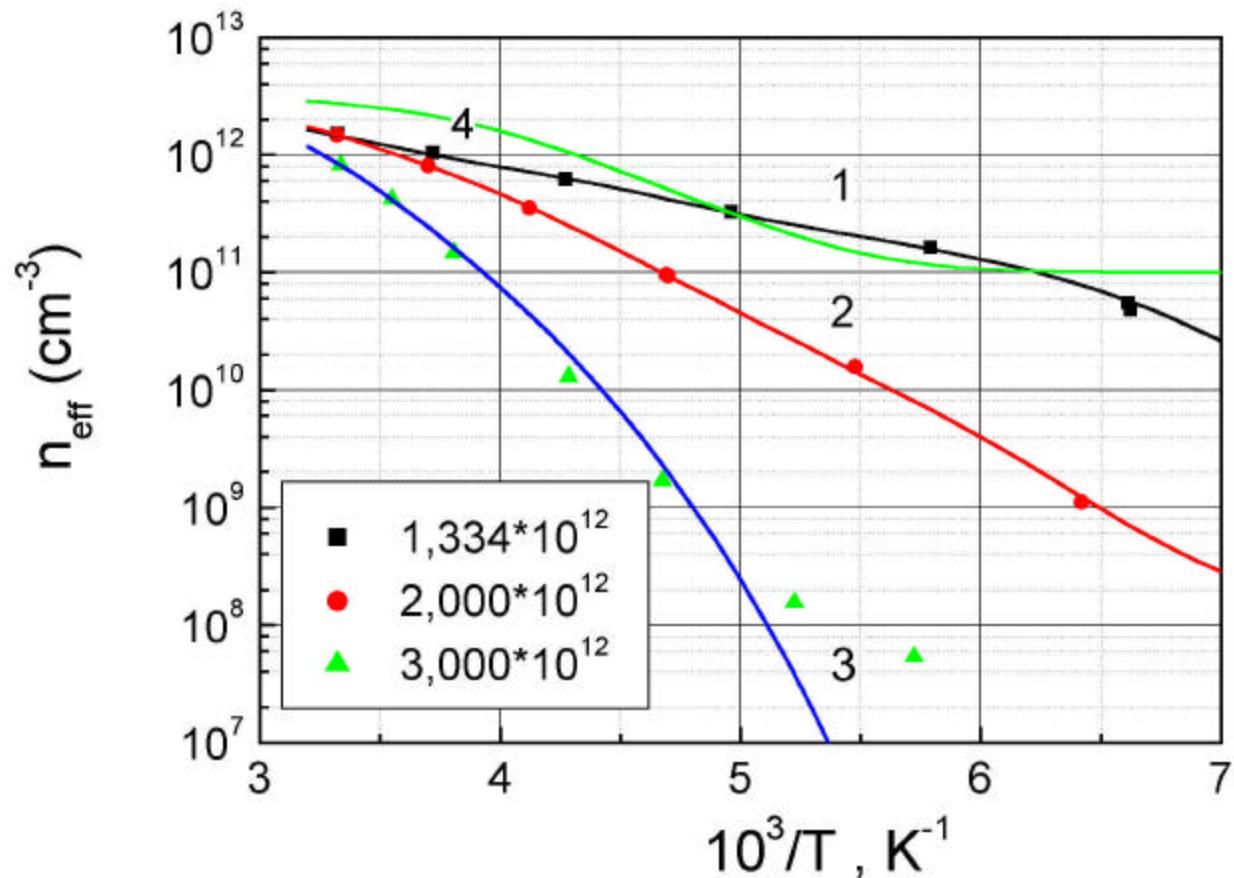


Fig. 4. The dependence of effective concentration of electrons on reciprocal temperature for n-Si (NTD) after irradiation by the fluence of fast-pile neutrons:

1 -- $1.33 \cdot 10^{12}$; 2 -- $2.0 \cdot 10^{12}$; 3 -- $3.0 \cdot 10^{12} \text{ n}^0 \cdot \text{cm}^{-2}$; 4 -- the concentration of electrons in the n-Si conducting matrix with the fluence $2 \cdot 10^{12} \text{ n}^0 \cdot \text{cm}^{-2}$

Table 2. Calculated concentration (N_a) and energy of levels (E_a) for radiation defects in the conducting matrix n-Si (NTD) irradiated by various doses of fast-pile neutrons (F); N_b is a concentration of screening centers outside the damage region of defect clusters with an average radius R_1

\mathbf{F} (n ^o · cm ⁻²)	n _o (cm ⁻³)	N _b (cm ⁻³)	N _a (cm ⁻³)	E _c -E _a (eV)	R ₁ (Å)
3.67· 10 ¹¹	2.67· 10 ¹²	2.52· 10 ¹²	6.0· 10 ¹¹	0.18	36
4.67· 10 ¹¹	2.68· 10 ¹²	2.52· 10 ¹²	7.0· 10 ¹¹	0.18	57
5.4· 10 ¹¹	2.64· 10 ¹²	2.51· 10 ¹²	7.95· 10 ¹¹	0.18	58
7.33· 10 ¹¹	2.51· 10 ¹²	2.33· 10 ¹²	1.08· 10 ¹²	0.19	64
		2.05· 10 ¹²	1.0· 10 ¹²	0.315	
1.33· 10 ¹²	2.35· 10 ¹²	1.05· 10 ¹²	3.0· 10 ¹¹	0.261	60
		7.5· 10 ¹¹	1.9· 10 ¹²	0.204	
2.0· 10 ¹²	3.07· 10 ¹²	2.57· 10 ¹²	2.47· 10 ¹²	0.36	76
3.0· 10 ¹²	3.07· 10 ¹²	2.32· 10 ¹²	1.8· 10 ¹²	0.405	86
		5.2· 10 ¹¹	0.9· 10 ¹²	0.39	
4.0· 10 ¹²	2.38· 10 ¹²	1.48· 10 ¹²	1.2· 10 ¹²	0.39	92
6.67· 10 ¹²	2.51· 10 ¹²	2.44· 10 ¹²	1.75· 10 ¹²	0.43	92
1.33· 10 ¹³	2.79· 10 ¹²	2.79· 10 ¹²	2.78· 10 ¹²	0.62	-